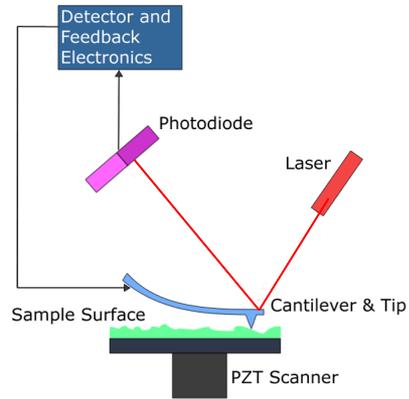


# Hydrogel Probes for Atomic Force Microscopy

Melissa Cadena

Mentor: Tejank Shah

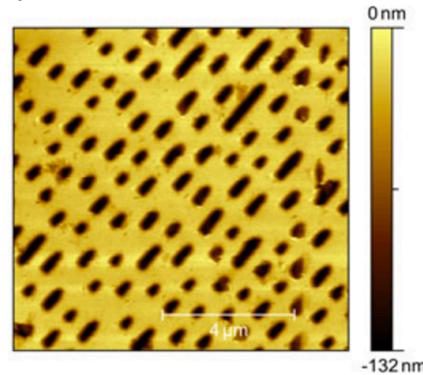
PI: Dr. Stefan Zauscher



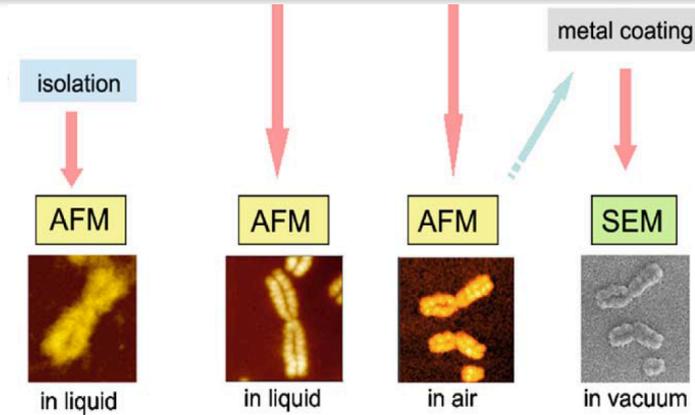
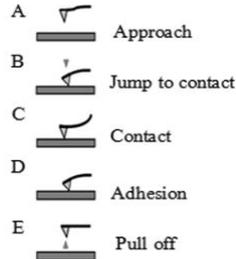
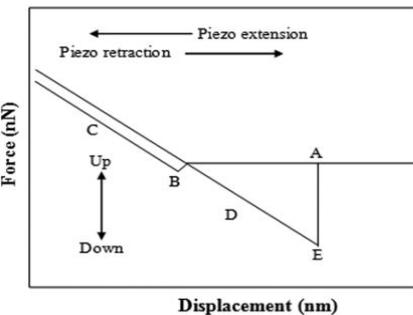
AFM measures a sample by detecting the movements of the cantilever across the sample surface

## Advantages

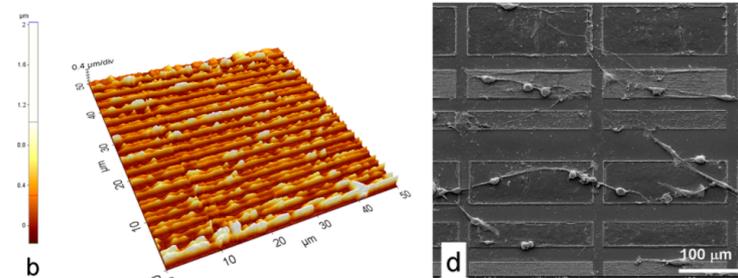
AFM image of DVD stamp imprinted into a PMMA layer



Detects forces the tip experiences as it comes to contact with the sample

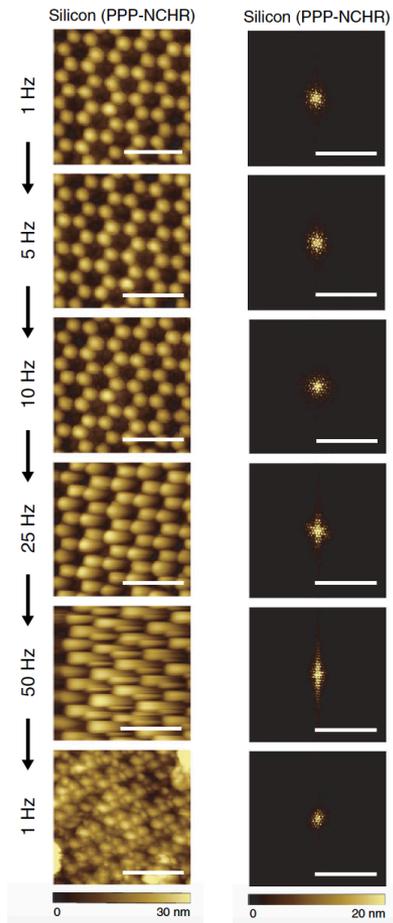


- Human Chromosomes imaged in ambient air and liquid by the AFM and in vacuum by SEM. AFM does not require metal coating of sample.

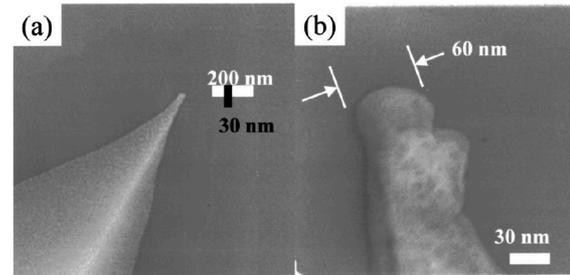


- OLN-93 cells distributed on lamin-coated line structured PMMA. The AFM image (b) provides surface topography and better 3D resolution than SEM (d).

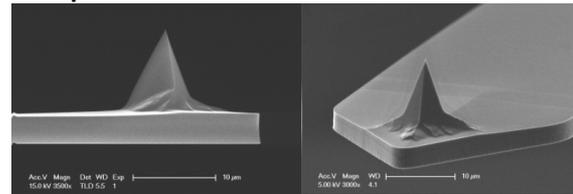
## 1. Unable to image at fast scan rates and observe increased artifacts



## 2. Short Tip Life



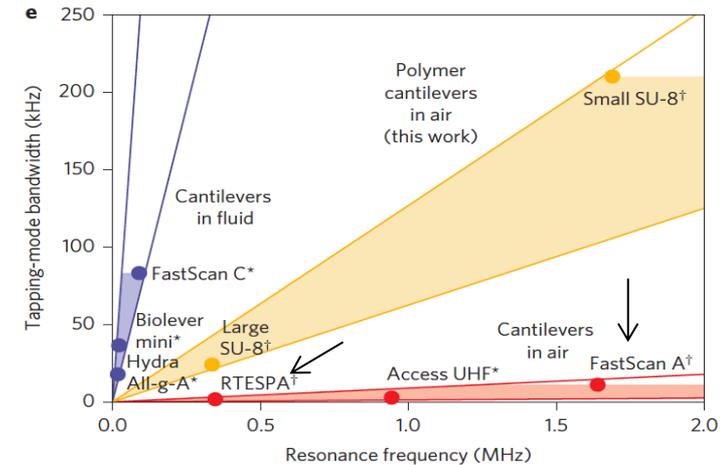
## 3. Limited tip geometries and aspect ratios



### Ideal Probe Characteristics:

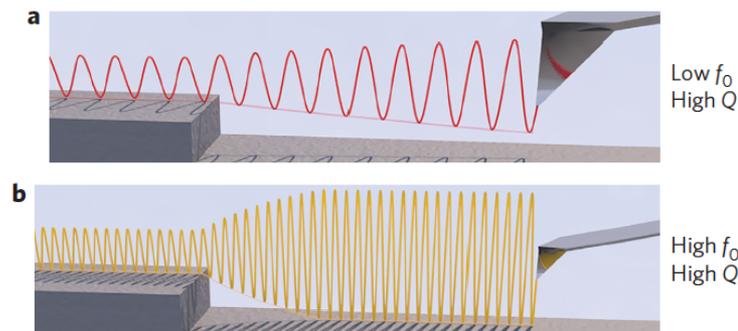
1. Image at fast scan rates
2. Reduce artifacts on sample
3. Minimal tip wear/be cheaper
4. Have different tip geometry and aspect ratios
5. Provide tunable mechanical properties

## 4. Limited Mechanical Tunability



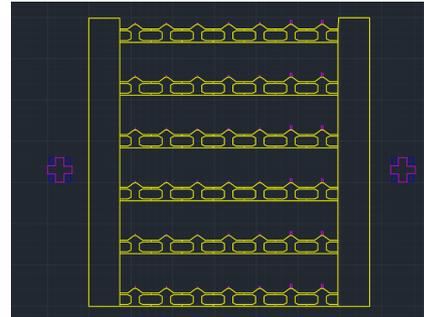
RTESPA has a low  $f_0$  and high Q (350) and FastScanA has a high  $f_0$  and high Q (180)

**Q factor:** Ratio of energy stored to energy lost per cycle at resonance

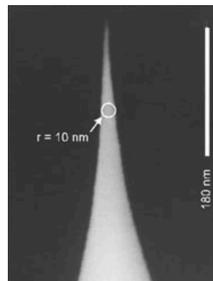


# Project Goals

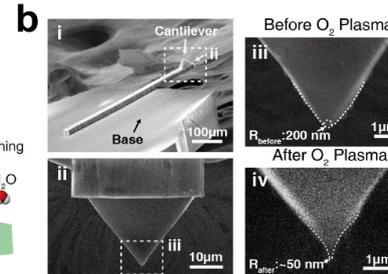
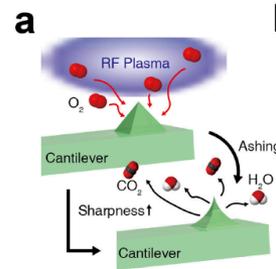
- Replicate Lee's procedure using Nicolas Wainwright's mask design and a modified mask



- Test the effect of oxygen plasma ashing on tip radius

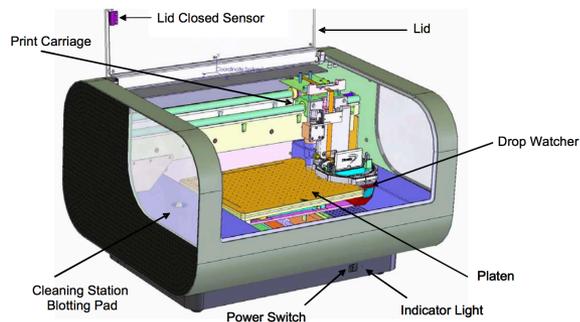


Silicon tip with 10 nm tip radius

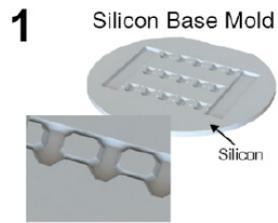


Hydrogel tip with 50 nm tip radius

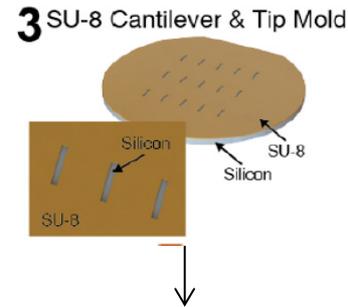
- Controllably print PEGDA on tipless cantilevers using an inkjet printer



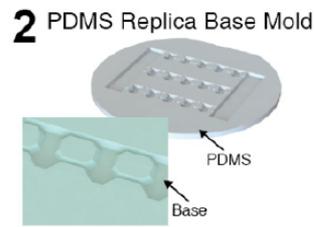
<sup>1</sup>J. Lee, *JMEMS Letters*, 2017; <sup>2</sup>Nano and More AFM Probes, SSS-FM Probes; <sup>3</sup>Fuji Film, *Dimatix Material Printer User Manual*, 2007



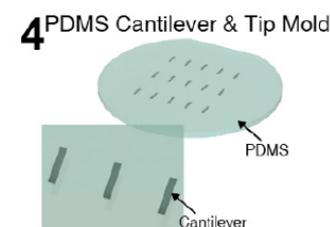
Photolithography and Deep Reactive Ion Etching on silicon wafer to achieve 150  $\mu\text{m}$  deep chip mold



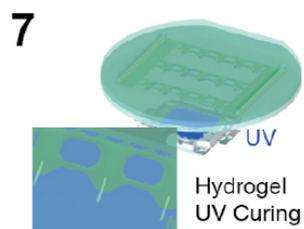
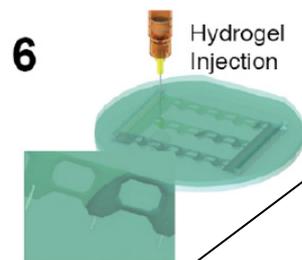
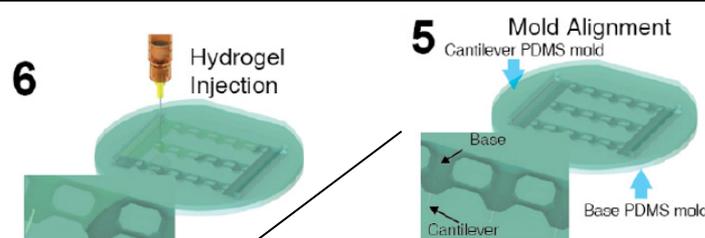
Photolithography and KOH etching of silicon wafer with 400nm silicon dioxide layer. Then pattern wafer with SU-8 to make aligned negative cantilever and tip mold



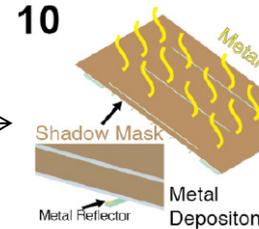
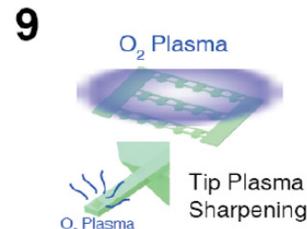
Treat with 1H, 1H, 2H, 2H-perfluorodecyltriethoxysilane (PFDTES) and replicate twice with PDMS to obtain 150  $\mu\text{m}$  deep chip mold



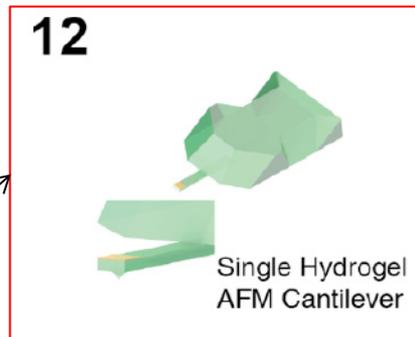
Treat with PFDTES and replicate twice with PDMS to obtain negative cantilever and tip mold



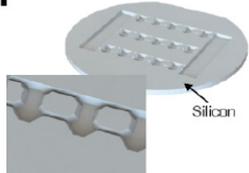
Demolding



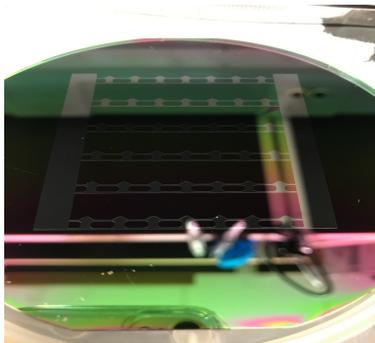
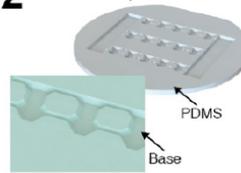
Cutting



1 Silicon Base Mold



2 PDMS Replica Base Mold



150 μm deep chip mold

Treat with PFDTES and replicate with PDMS



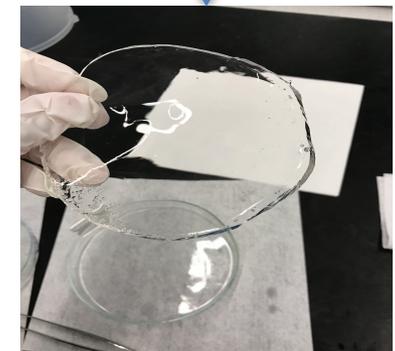
Positive 150 μm PDMS chip mold array



(1) Treat with PFDTES and replicate with PDMS  
(2) Plasma ash, treat with PFDTES and replicate with PDMS

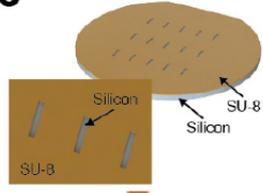
### Proposed Solution:

- (1) Plasma ash for longer and with more power, place in vacuum for longer
- (2) Plasma ash for longer and with more power, place in vacuum oven

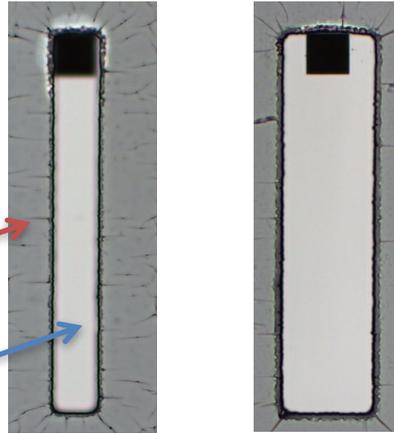


PDMS mold with no chip features

### 3 SU-8 Cantilever & Tip Mold



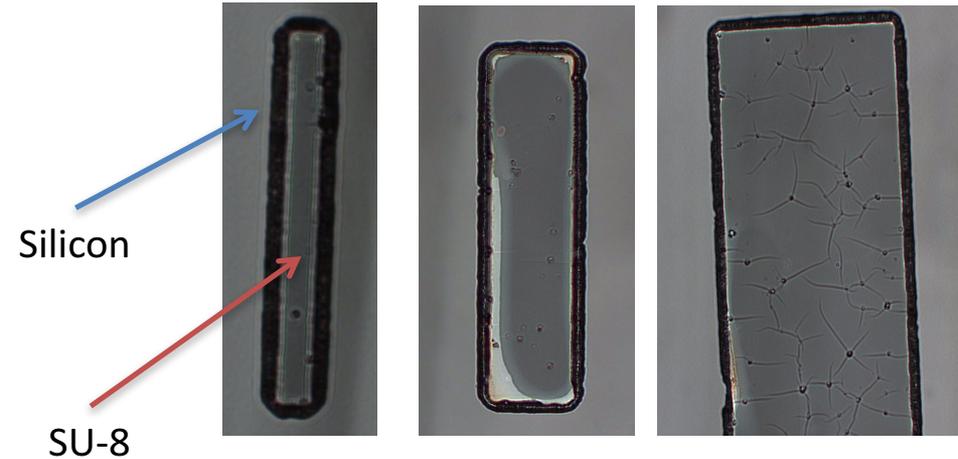
### Tipped Cantilevers



SU-8

Silicon

### Tipless Cantilevers



Silicon

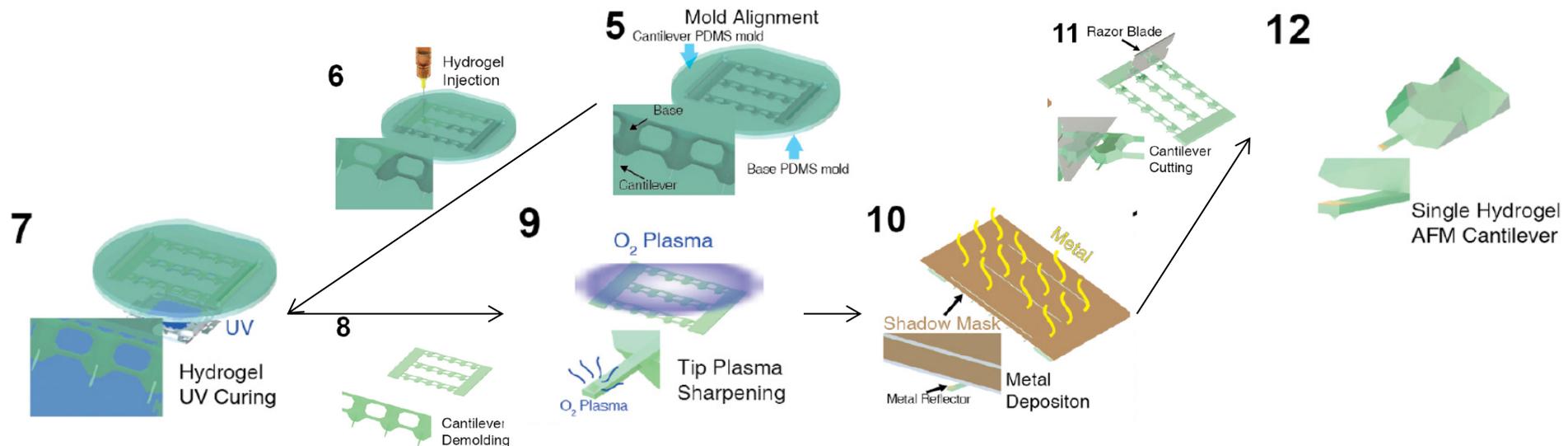
SU-8

- Three different dimensioned cantilevers are present
- No deformities present



- Three different dimensioned cantilevers are present
- Deformed cantilevers present as a result of poor SU-8 adhesion
- 71% of cantilevers can be used

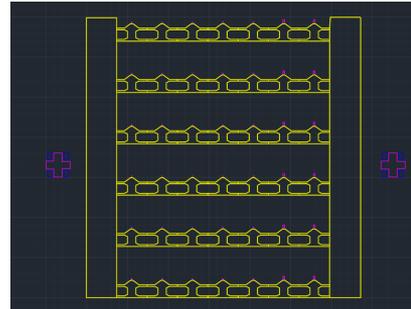
- Determine the best method for PDMS molding from PDMS master mold
- Continue batch fabrication approach to fabricate tip and tipless hydrogel probes:



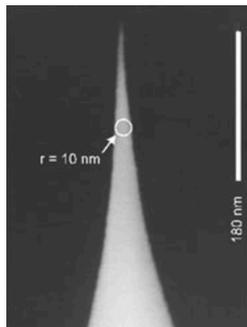
- Quantify mechanical properties of hydrogel probe
- Assess the force-indentation curves on a standard sample with different types of probes

# Project Goals

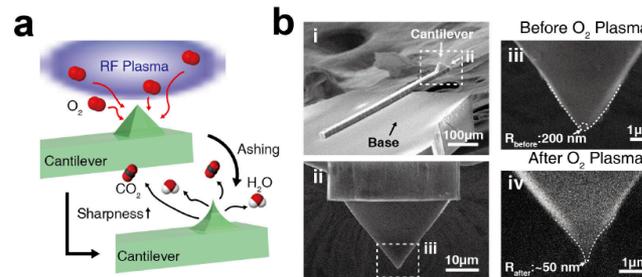
- Replicate Lee's procedure using Nicolas Wainwright's mask design and a modified mask



- Test the effect of oxygen plasma ashing on tip radius



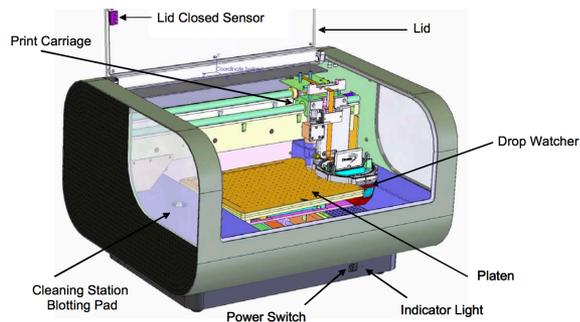
Silicon tip with 10 nm tip radius



Hydrogel tip with 50 nm tip radius

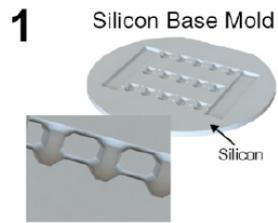


- Controllably print PEGDA on tipless cantilevers using an inkjet printer

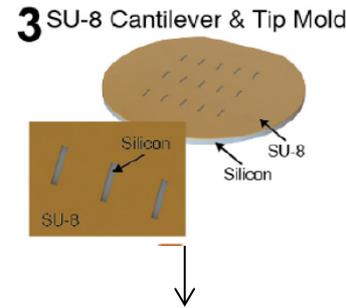


<sup>1</sup>J. Lee, *JMEMS Letters*, 2017; <sup>2</sup>Nano and More AFM Probes, SSS-FM Probes; <sup>3</sup>Fuji Film, *Dimatix Material Printer User Manual*, 2007

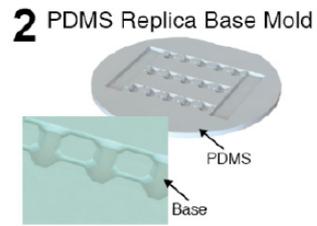
# Batch Fabrication Approach



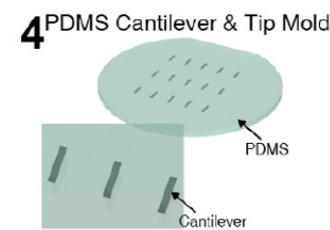
Photolithography and Deep Reactive Ion Etching on silicon wafer to achieve 150  $\mu\text{m}$  deep chip mold



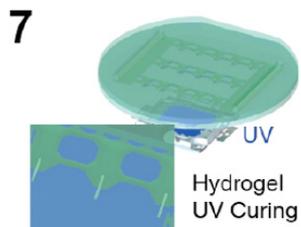
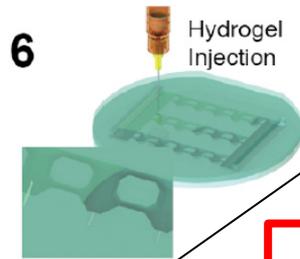
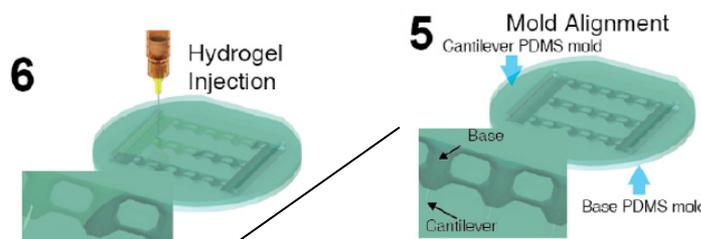
Photolithography and KOH etching of silicon wafer with 400nm silicon dioxide layer. Then pattern wafer with SU-8 to make aligned negative cantilever and tip mold



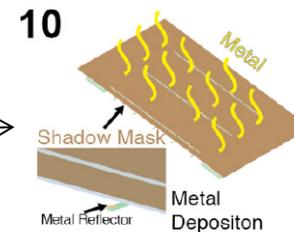
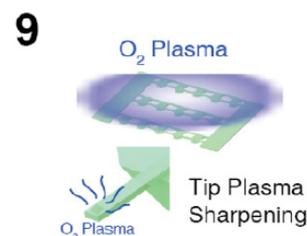
Treat with 1H, 1H, 2H, 2H-perfluorodecyltriethoxysilane (PFDTES) and replicate twice with PDMS to obtain 150  $\mu\text{m}$  deep chip mold



Treat with PFDTES and replicate twice with PDMS to obtain negative cantilever and tip mold



Demolding



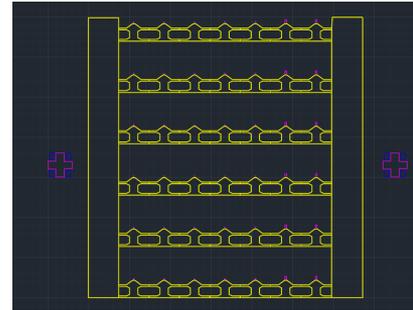
Cutting



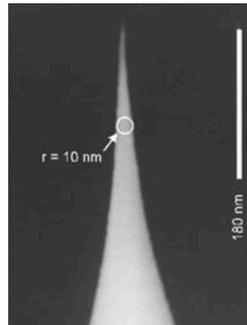
Time

# Project Goals

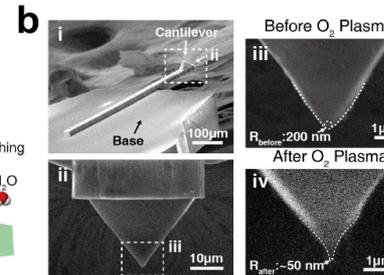
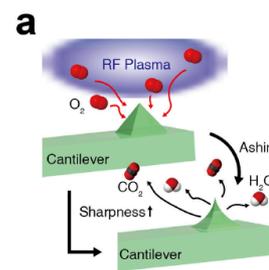
- Replicate Lee's procedure using Nicolas Wainwright's mask design and a modified mask



- Test the effect of oxygen plasma ashing on tip radius

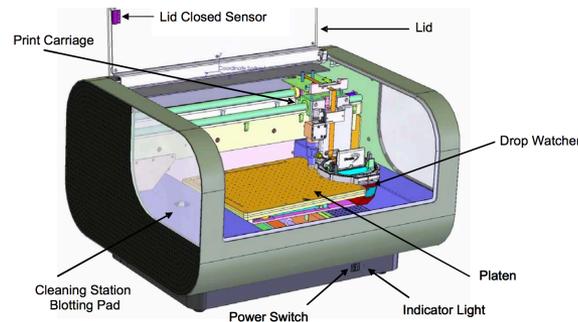


Silicon tip with 10 nm tip radius



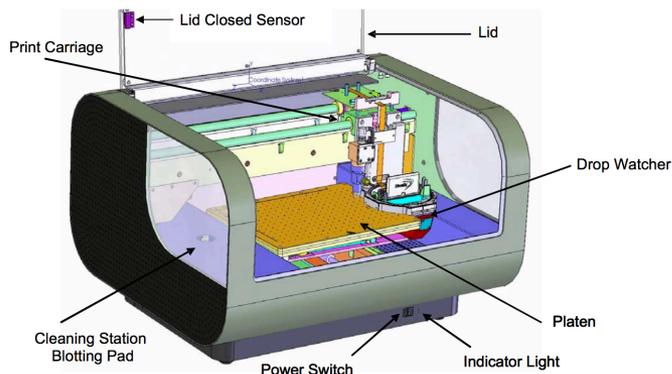
Hydrogel tip with 50 nm tip radius

- Controllably print PEGDA on tipless cantilevers using an inkjet printer

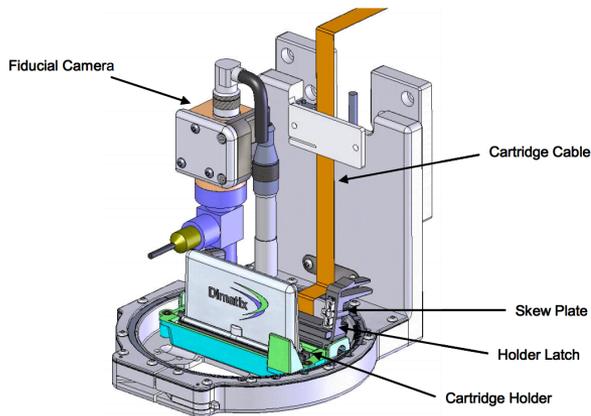


# Can we control tip radii with batch fabrication?

**Proposal:** Controlling droplet volume through inkjet printing



Dimatix Materials Printer, 2800 series



**Long Term Goal:** To controllably print PEGDA spherical tips on tip-less cantilevers

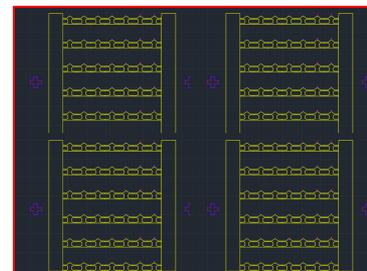
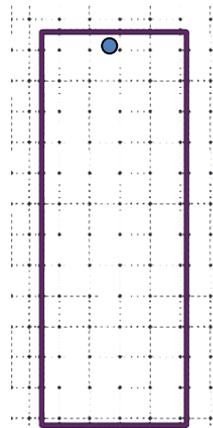
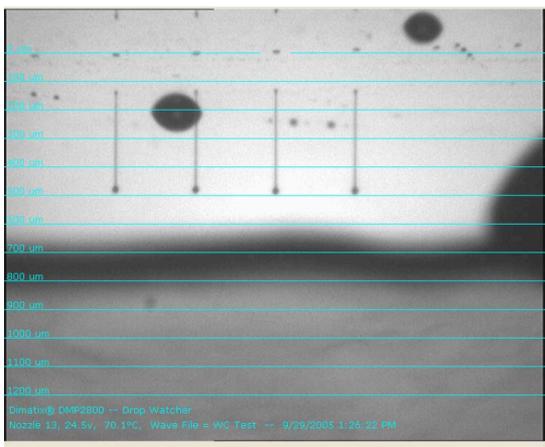


Thanks Dan Joh!

Can vary different parameters and observe changes through drop watcher

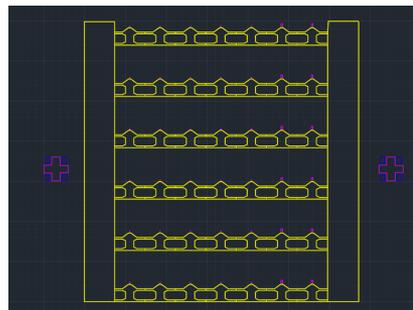
Can use a predefined design, create your own design, or import a specific pattern

Can batch fabricate a pattern because of large printing area (8.5 inches x 11 inches)

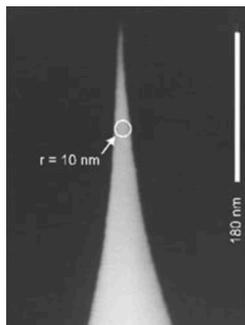


# Project Goals

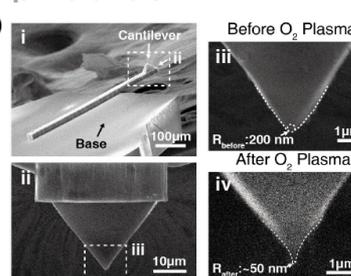
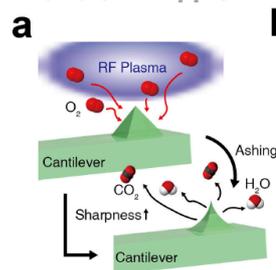
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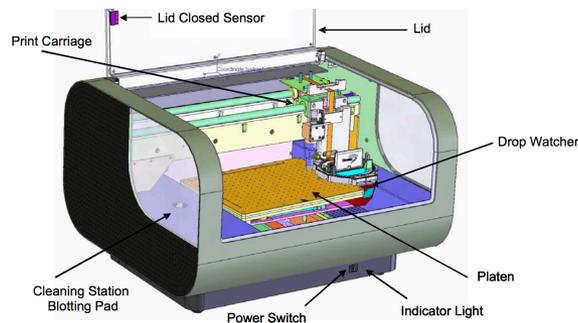


Silicon tip with 10 nm tip radius



Hydrogel tip with 50 nm tip radius

- Controllably print PEGDA on tipless cantilevers using an inkjet printer



# Acknowledgements



## Zauscher Lab

Dan French  
Neil Gupta  
Salena Huang  
Luis Navarro  
Zehra Parlak

## MRSEC

Miquella Chavez  
Katie Krieger  
Catherine Reyes

## Chilkoti Lab

Dan Joh

## SMIF

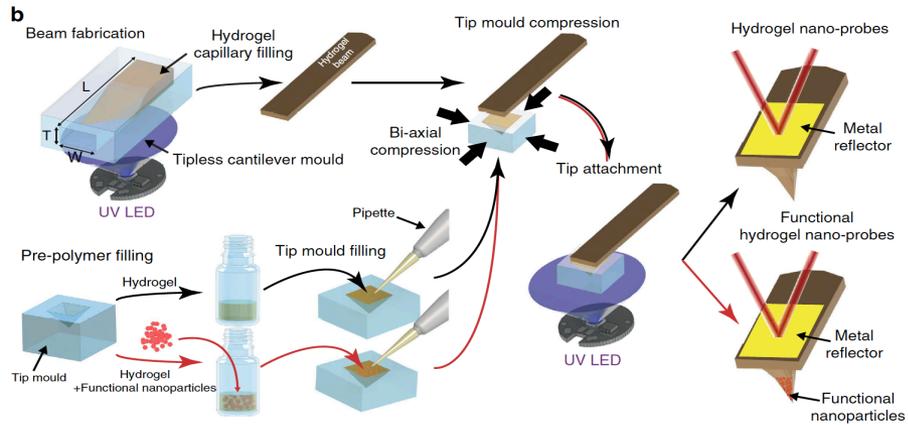
Kirk Bryson  
Jay Dalton



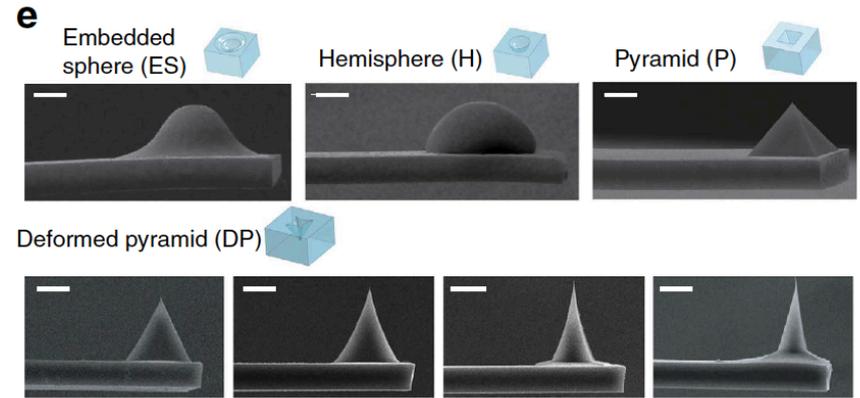
## Contact Information:

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University of Michigan  
[mcadena@umich.edu](mailto:mcadena@umich.edu)  
LinkedIn

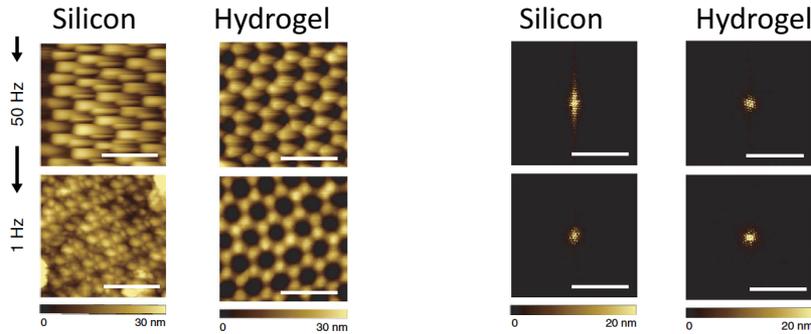
# Extra Slides



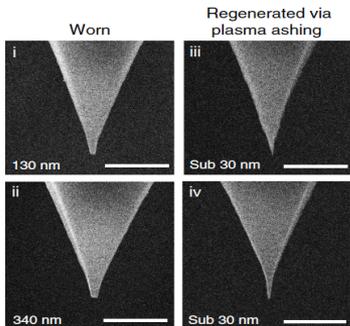
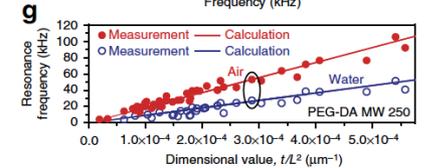
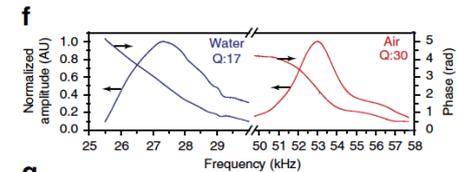
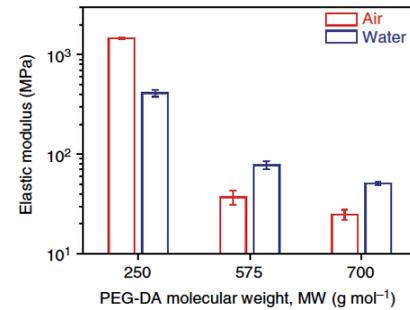
Different tip geometries and aspect ratios achievable



Hydrogel nanoprobe image well at fast rates and minimize distortions on the sample

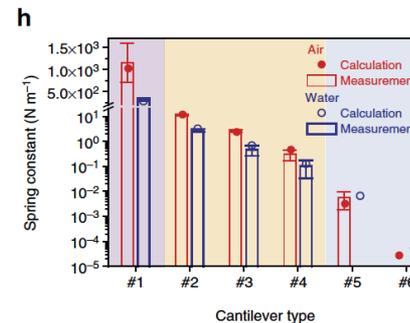


Can tune mechanical properties



Can regenerate worn hydrogel tips through oxygen plasma ashing

1. J. Lee, *Nature Comm*, 2016



**Limitation:** not a scalable procedure

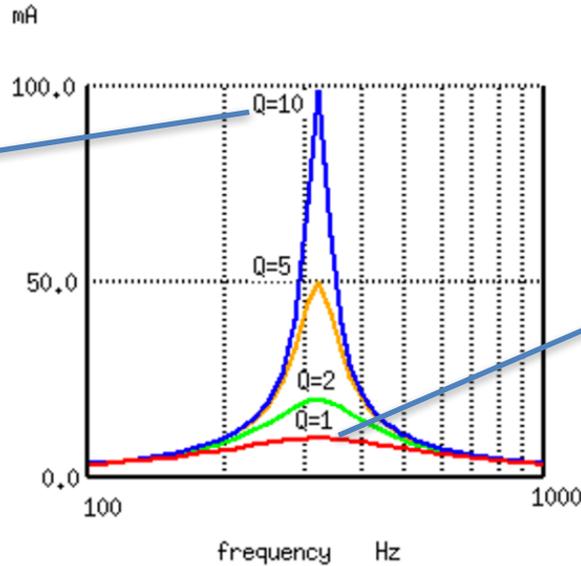
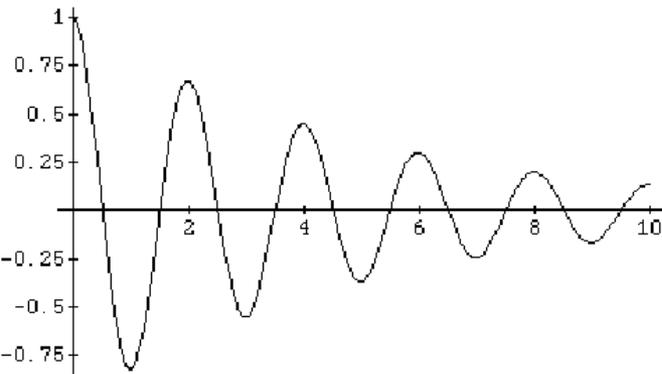
# Q-Factor

- Describes the ratio of energy stored to energy lost per cycle at resonance

High Q : More energy stored than lost



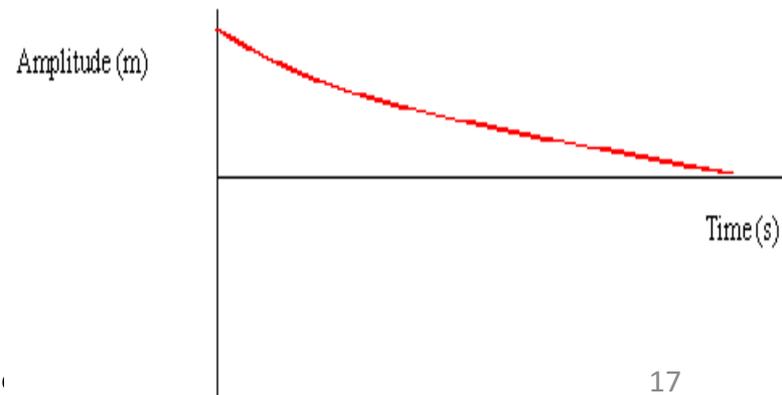
High Q = Underdamped System



Low Q : More energy lost than stored



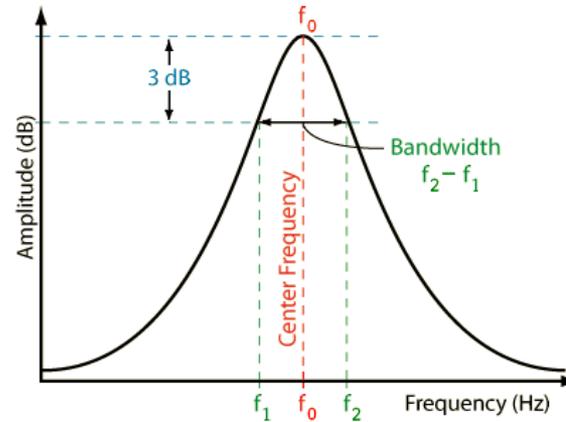
Low Q = Overdamped System



1. All About Circuits, Chap 6
2. University of Massachusetts
3. Antonine Education, Oscillati

# Q-Factor

Proportional to:  $Q = \frac{f_0}{B}$



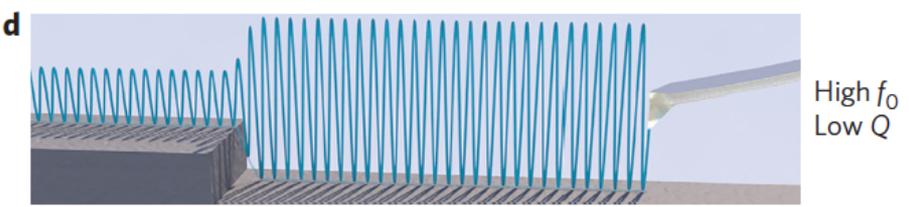
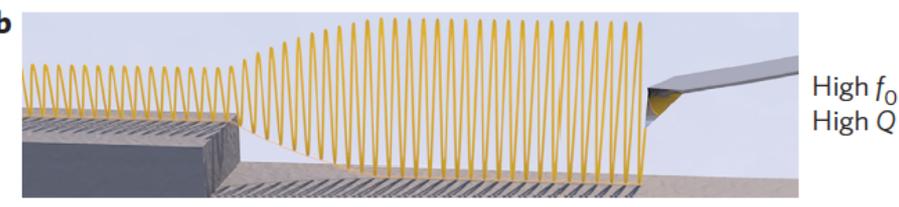
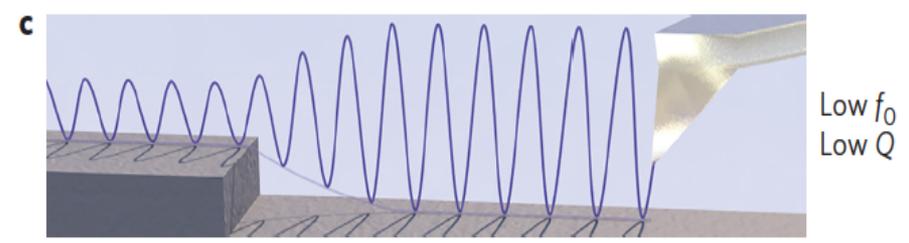
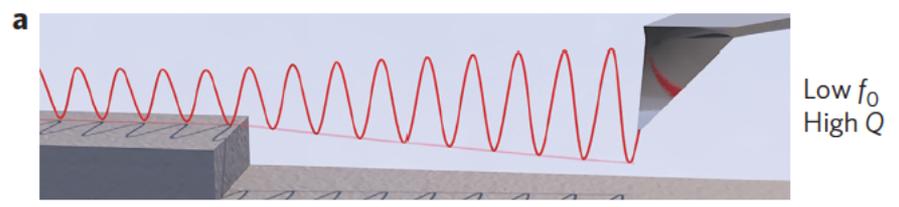
$f_0$  : Frequency where maximum amplitude is observed

**B**: Bandwidth, range of frequencies for which the oscillator resonates

Why does this matter in AFM?



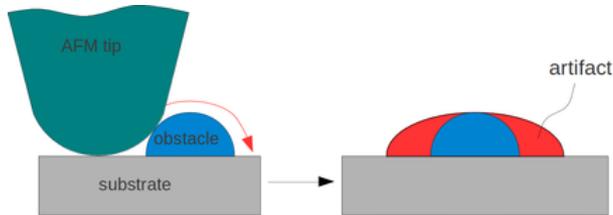
Q and  $f_0$  determine how quickly a topographical change is detected and subsequently measured



Want this

1. Tontechnik-Rechner-Sengpielaudio
2. J. Adams, *Nature Nanotech*, 2015

# Shortcomings of AFM



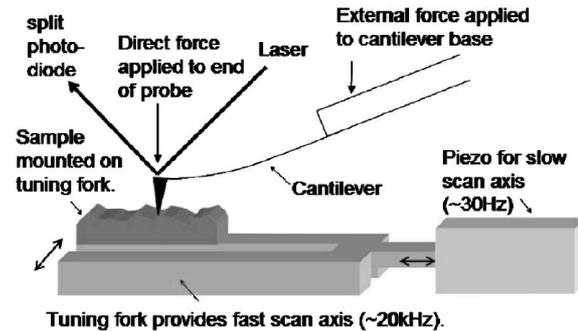
1. Artifacts on sample caused by worn AFM tip

**Solution:** Change mode (i.e. from contact to tapping mode) to minimize tip damage or change tip

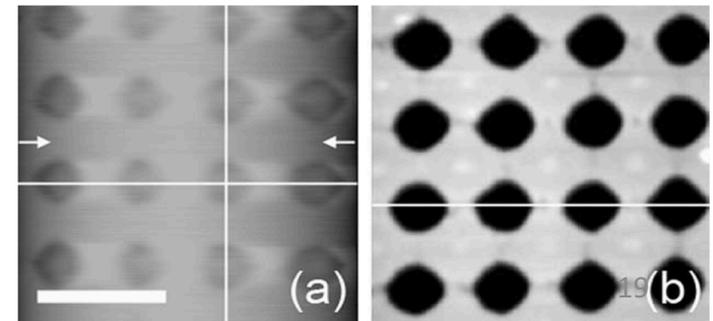
**Pro:** Minimizes sample damage, tip wear, and artifacts because reduced tip sample interaction time (1  $\mu$ s vs 1 ms)

2. Slow scan rate (12 frames/s) and small image area (250 x 250 nm)

**Solution:** VideoAFM or High Speed AFM (HSAFM)



**Con:** Not good at imaging topography that changes rapidly



1. Atomic Force Microscopy, Wikipedia, 2017
2. A.D.L. Humphris, *Appl. Phys. Lett.*, 2005
3. J.K. Hobbs, *The Analyst*, 2005